



S. Royau
12 7/19/02

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kiyoichi SUWA

Application No.: 09/729,339

Filed: December 5, 2000

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND
METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES

Group Art Unit: 2818

Examiner: Q. D. Hoang

Docket No.: 108057

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AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed January 4, 2002, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 1 and 9-10 without prejudice to or disclaimer of the subject matter contained therein. Applicant reserves the right to file a Divisional Application to pursue claims 9-10.

Please replace claims 2, 4-7 and 11 as follows:

(Amended) A mask comprising:

a circuit pattern to be transferred to a substrate via an optical system; and

an inspection pattern to be used for a measurement of a line width of a pattern

transferred to said substrate,

wherein said inspection pattern includes:

Q1
sub
B1

PR
KP